

Shota Nunomura

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56
papers

1,652
citations

22
h-index

40
g-index

59
ext. papers

1,794
ext. citations

3.6
avg, IF

4.6
L-index

#	Paper	IF	Citations
56	Phonon spectrum in a plasma crystal. <i>Physical Review Letters</i> , 2002 , 89, 035001	7.4	160
55	Instability of Dust Particles in a Coulomb Crystal due to Delayed Charging. <i>Physical Review Letters</i> , 1999 , 83, 1970-1973	7.4	150
54	Dispersion relations of longitudinal and transverse waves in two-dimensional screened Coulomb crystals. <i>Physical Review E</i> , 2002 , 65, 066402	2.4	135
53	Laser-excited mach cones in a dusty plasma crystal. <i>Physical Review E</i> , 2000 , 62, 4162-76	2.4	126
52	Wave spectra in solid and liquid complex (dusty) plasmas. <i>Physical Review Letters</i> , 2005 , 94, 045001	7.4	76
51	Self-diffusion in a liquid complex plasma. <i>Physical Review Letters</i> , 2006 , 96, 015003	7.4	74
50	Polarization of wave modes in a two-dimensional hexagonal lattice using a complex (dusty) plasma. <i>Physical Review E</i> , 2003 , 68, 035401	2.4	66
49	Effects of Ion Flow by E _B Drift on Dust Particle Behavior in Magnetized Cylindrical Electron Cyclotron Resonance Plasmas. <i>Japanese Journal of Applied Physics</i> , 1997 , 36, 877-883	1.4	56
48	Characterization of high-pressure capacitively coupled hydrogen plasmas. <i>Journal of Applied Physics</i> , 2007 , 102, 093306	2.5	56
47	Heat transfer in a two-dimensional crystalline complex (dusty) plasma. <i>Physical Review Letters</i> , 2005 , 95, 025003	7.4	55
46	Nonlinear compressional pulses in a 2D crystallized dusty plasma. <i>Physical Review Letters</i> , 2002 , 88, 215002	7.4	46
45	Single step method to deposit Si quantum dot films using H ₂ +SiH ₄ VHF discharges and electron mobility in a Si quantum dot solar cell. <i>Surface and Coatings Technology</i> , 2007 , 201, 5468-5471	4.4	44
44	Confinement and structure of electrostatically coupled dust clouds in a direct current plasma sheath. <i>Physics of Plasmas</i> , 1998 , 5, 3517-3523	2.1	44
43	Mie scattering enhanced near-infrared light response of thin-film silicon solar cells. <i>Applied Physics Letters</i> , 2010 , 97, 063507	3.4	38
42	Gas temperature and surface heating in plasma enhanced chemical-vapour-deposition. <i>Plasma Sources Science and Technology</i> , 2006 , 15, 783-789	3.5	37
41	Fabrication of Nanoparticle Composite Porous Films Having Ultralow Dielectric Constant. <i>Japanese Journal of Applied Physics</i> , 2005 , 44, L1509-L1511	1.4	37
40	In situ simple method for measuring size and density of nanoparticles in reactive plasmas. <i>Journal of Applied Physics</i> , 2006 , 99, 083302	2.5	30

39	Nonlinear longitudinal waves in a two-dimensional screened Coulomb crystal. <i>Physical Review E</i> , 2003 , 68, 026407	2.4	29
38	Dynamic behaviors of dust particles in the plasma sheath boundary. <i>Physics of Plasmas</i> , 2001 , 8, 1886-1892	2.1	27
37	Passivation property of ultrathin SiO _x :H / a-Si:H stack layers for solar cell applications. <i>Solar Energy Materials and Solar Cells</i> , 2018 , 185, 8-15	6.4	26
36	Time-dependent gas phase kinetics in a hydrogen diluted silane plasma. <i>Applied Physics Letters</i> , 2009 , 94, 071502	3.4	26
35	Positive ion polymerization in hydrogen diluted silane plasmas. <i>Applied Physics Letters</i> , 2008 , 93, 231502	3.4	26
34	Impact of intrinsic amorphous silicon bilayers in silicon heterojunction solar cells. <i>Journal of Applied Physics</i> , 2018 , 124, 103102	2.5	22
33	Precursor flux-dependent microstructure of thin-film silicon prepared by hydrogen diluted silane discharge plasmas. <i>Journal Physics D: Applied Physics</i> , 2009 , 42, 185210	3	20
32	Observation of the Structure and its Formation Process of a New Volumetric Coulomb Cloud Composed of Different Multiple Dust Layers. <i>Japanese Journal of Applied Physics</i> , 1997 , 36, L949-L951	1.4	19
31	Double-sided TOPCon solar cells on textured wafer with ALD SiO _x layer. <i>Solar Energy Materials and Solar Cells</i> , 2020 , 207, 110357	6.4	19
30	Plasma-Induced Electronic Defects: Generation and Annihilation Kinetics in Hydrogenated Amorphous Silicon. <i>Physical Review Applied</i> , 2018 , 10,	4.3	17
29	Rapid transport of nano-particles having a fractional elementary charge on average in capacitively-coupled rf discharges by amplitude-modulating discharge voltage. <i>Faraday Discussions</i> , 2008 , 137, 127-38; discussion 193-204	3.6	16
28	Impact of silicon wafer thickness on photovoltaic performance of crystalline silicon heterojunction solar cells. <i>Japanese Journal of Applied Physics</i> , 2018 , 57, 08RB10	1.4	15
27	Observation of Transverse Dust Lattice Wave Excited by Unstable Vertical Oscillations of Dust Particles in an Ion Sheath with Low Gas Pressure. <i>Japanese Journal of Applied Physics</i> , 2000 , 39, L551-L553	1.4	15
26	Charge trapping in mixed organic donor-acceptor semiconductor thin films. <i>Advanced Materials</i> , 2014 , 26, 7555-60	2.4	14
25	Nanoparticle coagulation in fractionally charged and charge fluctuating dusty plasmas. <i>Physics of Plasmas</i> , 2008 , 15, 080703	2.1	13
24	Electronic properties of ultrathin hydrogenated amorphous silicon. <i>Applied Physics Express</i> , 2017 , 10, 081401	2.4	12
23	In-situ detection of interface defects in a-Si:H/c-Si heterojunction during plasma processing. <i>Applied Physics Express</i> , 2019 , 12, 051006	2.4	11
22	Impact of band tail distribution on carrier trapping in hydrogenated amorphous silicon for solar cell applications. <i>Journal of Non-Crystalline Solids</i> , 2016 , 436, 44-50	3.9	11

21	In situ Photocurrent Measurements of Thin-Film Semiconductors during Plasma-Enhanced Chemical Vapor Deposition. <i>Applied Physics Express</i> , 2013 , 6, 126201	2.4	11
20	Hydrogen atom kinetics in capacitively coupled plasmas. <i>Plasma Sources Science and Technology</i> , 2017 , 26, 055018	3.5	10
19	Progress and perspectives in dry processes for nanoscale feature fabrication: fine pattern transfer and high-aspect-ratio feature formation. <i>Japanese Journal of Applied Physics</i> , 2019 , 58, SE0802	1.4	9
18	In-situ characterization of trapped charges in amorphous semiconductor films during plasma-enhanced chemical vapor deposition. <i>AIP Advances</i> , 2014 , 4, 097110	1.5	9
17	Roles of hydrogen atoms in p-type Poly-Si/SiO _x passivation layer for crystalline silicon solar cell applications. <i>Japanese Journal of Applied Physics</i> , 2019 , 58, 050915	1.4	7
16	Role of silicon surface, polished <100> and <111> or textured, on the efficiency of double-sided TOPCon solar cells. <i>Progress in Photovoltaics: Research and Applications</i> , 2020 , 28, 1001-1011	6.8	7
15	Transient Phenomena in Plasma-Enhanced Chemical Vapor Deposition Processes of Thin-Film Silicon. <i>Japanese Journal of Applied Physics</i> , 2010 , 49, 106102	1.4	7
14	Formation of electronic defects in crystalline silicon during hydrogen plasma treatment. <i>AIP Advances</i> , 2019 , 9, 045110	1.5	5
13	Structural Formation and Stability of Coulomb Clouds in Medium through Low Gas Pressure Range 2000 , 337-344		3
12	Real-time monitoring of surface passivation of crystalline silicon during growth of amorphous and epitaxial silicon layer. <i>Journal of Applied Physics</i> , 2020 , 128, 033302	2.5	3
11	Hydrogen-induced defects in crystalline silicon during growth of an ultrathin a-Si:H layer. <i>Japanese Journal of Applied Physics</i> , 2020 , 59, SHHE05	1.4	3
10	Hydrogen passivation effect on p-type poly-Si/SiO _x stack for crystalline silicon solar cells 2019 ,		2
9	Progress and perspectives in dry processes for leading-edge manufacturing of devices: toward intelligent processes and virtual product development. <i>Japanese Journal of Applied Physics</i> , 2019 , 58, SE0804	1.4	2
8	Particle simulation on multiple dust layers of Coulomb cloud in cathode sheath edge. <i>European Physical Journal D</i> , 1998 , 48, 239-244		2
7	Passivating antireflection coating of crystalline silicon using i/n a-Si:H/SiN trilayer. <i>Journal of Physics and Chemistry of Solids</i> , 2021 , 156, 110127	3.9	2
6	Towards solar cells with black silicon texturing passivated by a-Si:H 2018 ,		1
5	Progress and perspectives in dry processes for emerging multidisciplinary applications: how can we improve our use of dry processes?. <i>Japanese Journal of Applied Physics</i> , 2019 , 58, SE0803	1.4	0
4	Ion-induced interface defects in a-Si:H/c-Si heterojunction: possible roles and kinetics of hot mobile hydrogens. <i>Japanese Journal of Applied Physics</i> , 2022 , 61, 056003	1.4	0

- 3 Response to Comment on Dynamic behaviors of dust particles in the plasma-sheath boundary [Phys. Plasmas 9, 1057 (2002)]. *Physics of Plasmas*, **2002**, 9, 1060-1061 2.1
- 2 Simulation on Structure and Dynamic Behavior of Dust Particles in a Direct Current Plasma-Sheath. *Journal of Plasma and Fusion Research*, **1999**, 75-CD, 234-257
- 1 Instabilities of Dust Particles Levitated in an Ion Sheath with Low Gas Pressure **2000**, 465-468